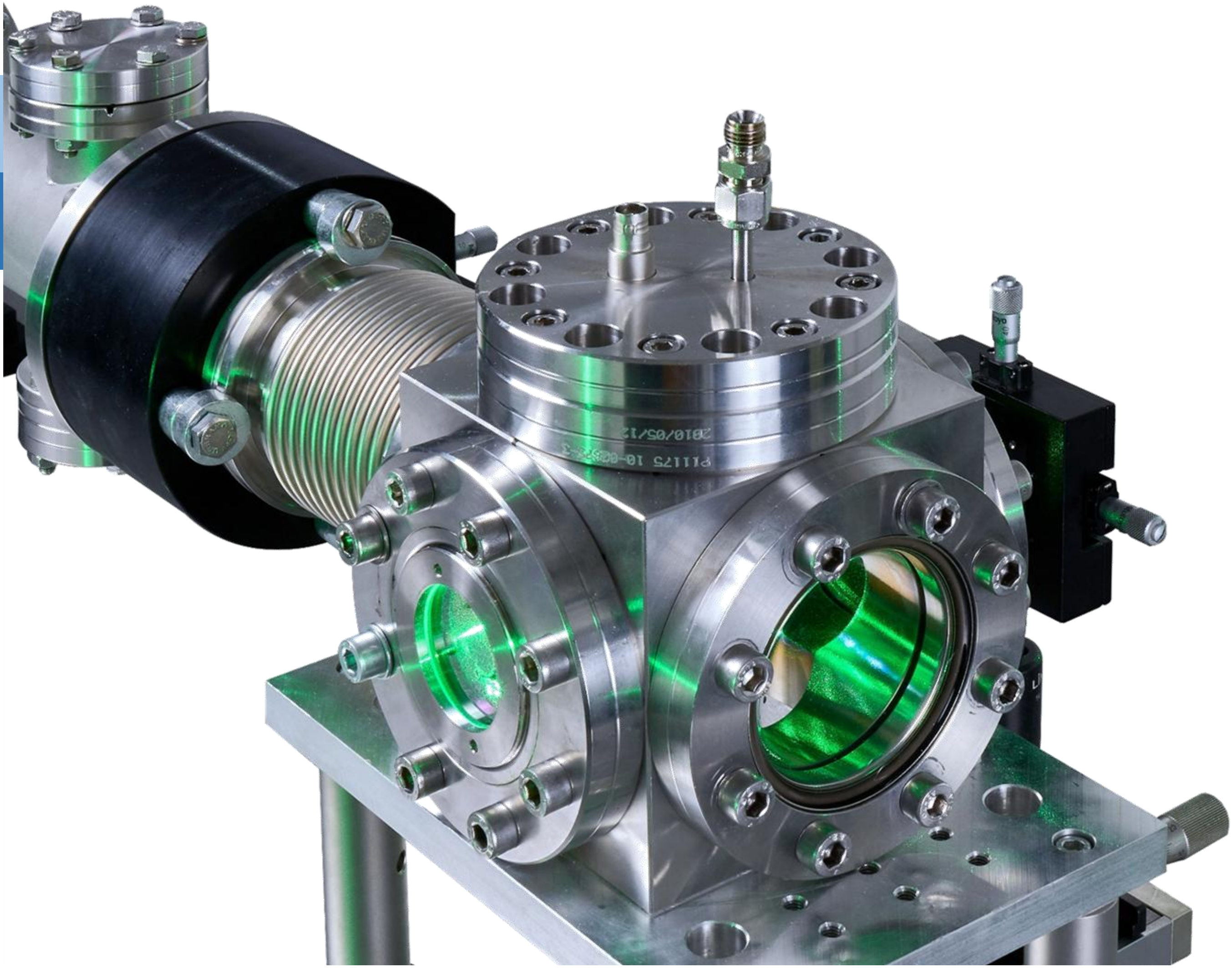
proLINE

COMPACT EUV LIGHT SOURCE

XUV

SXR



hp spectroscopy

proLINE

Features

Plasma-based EUV light source

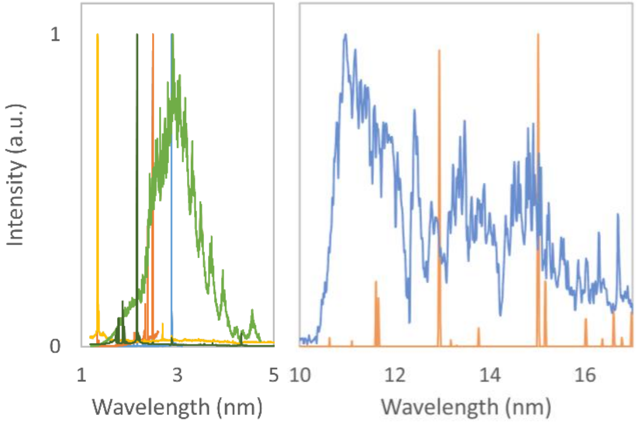
- high photon flux
- broadband or monochromatized output
- wide selection of wavelengths
- low debris through electrodeless setup
- 300um source size for high brightness

Ease of use

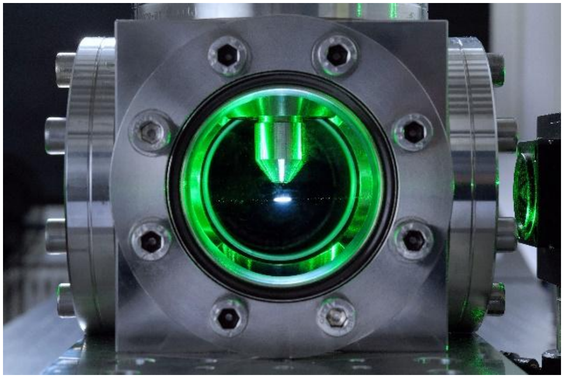
- compact footprint
- low cost of ownership (marginal gas flow rate)
- highly reliable, long-term stable EUV source
- optional integrated diagnostics

Applications

- EUV metrology
- mask defect inspection
- resist development
- EUV microscopy
- water-window microscopy



Characteristic plasma emission spectra of proLINE. Wavelength switching is fast and automated through gas selection and monochromator settings



XUV light source using a highly-reliable laser-produced plasma. Energy range 1-20nm/ 60-1200eV. Repetition rate 20Hz

proLINE

Specifications

Type	debris-free laser-produced plasma soft X-ray source
Target gas	krypton, nitrogen, xenon (others on request)
Repetition rate	20Hz
Source power stability	±1.5%
Wavelength range	1.5-6, 2.16, 2.48, 2.88, 13.0, 13.5nm (other wavelengths on request)
Emission angle	2pi (focusing unit available)
Vacuum compatibility	$<10^{-6}$mbar (UHV version available)
Laser safety class	1
Footprint	1m x 1m

	krypton	nitrogen	xenon
Energy range	1.5-6nm	2.48nm, 2.88nm	13.0nm, 13.5nm
Flux	$2\cdot10^{15}$ph/s/sr ($1\cdot10^{13}$ph/s/sr/eV at 450eV)	$1\cdot10^{14}$ph/s/sr	$7\cdot10^{14}$ph/s/sr
Output power (into 2pi sr)	200mW	10mW	70mW
Monochromatic flux (2% bandwidth) in 250um focus spot	$7\cdot10^{19}$ph/s/m^2	$2\cdot10^{19}$ph/s/m^2	$2\cdot10^{22}$ph/s/m^2

Contact us

HP SPECTROSCOPY GmbH
Forggenseestr. 25, 68219 Mannheim, Germany
tel +49 176 20949282, info@hp-spectroscopy.com
http://www.hp-spectroscopy.com

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